	Application No.	Applicant(s)
Notice of Allowability	10/710,870	PRATHER et al.
	Examiner	Art Unit
	Lee, Calvin	2818
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.		
1. This communication is responsive to <u>Appeal Brief filed on March 27, 2006</u> .		
2. The allowed claim(s) is/are <u>1-10</u> .		
3. The drawings filed on <u>09 August 2004</u> are accepted by the Examiner.		
4. Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).  a) All b) Some* c) None of the:  1. Certified copies of the priority documents have been received.  2. Certified copies of the priority documents have been received in Application No		
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Attachment(s)  1. Notice of References Cited (PTO-892)  2. Notice of Draftperson's Patent Drawing Review (PTO-948)  3. Information Disclosure Statements (PTO-1449 or PTO/SB/O Paper No./Mail Date  4. Examiner's Comment Regarding Requirement for Deposit of Biological Material	6. ☐ Interview Summary Paper No./Mail Dat 98), 7. ☑ Examiner's Amendn	e

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## **OFFICE ACTION**

## Examiner's Amendment

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. IN THE CLAIM: Claim 11 has been canceled due to nonelected without traverse dated 2/28/05.

## Allowable Subject Matter

- 2. Claims 1-10 are allowed. Following is the reason for allowance:
  The closest art, Lin et al '342 discloses sweeping (or applying pressure) the conductive paste 30 with a squeegee 40 across the wet photoresist layer 15, forcing the conductive paste 30 into openings 20, and removing the excess conductive paste 30 off photoresist mask 15. Lin et al, however, does not teach or suggest polishing the conductive polymer layer to remove excess conductive polymer material from a surface of the photoresist.
- 3. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance.

## **Contact Information**

4. Any inquiry concerning this communication from the Examiner should be directed to Calvin Lee at (571) 272-1896 from 7:00AM to 5:00PM (Monday-Thursday, Eastern Time). If attempts to reach the examiner by telephone are unsuccessful, Art Unit 2825's Supervisory Patent Examiner David C. Nelms can be reached at (571) 272-1787.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAG or Public PAIR. For more information about the PAIR system, see <a href="http://pair-direct.uspto.gov">http://pair-direct.uspto.gov</a> Should you have questions on access to the PAG system, contact the Electronic Business Center (EBC) at 1-866-217-9197.

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Dated: May 17, 2006

Andy Kuynet ANDY HUYNH PRIMARY EXAMINER